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SU et al.(10) **Pub. No.: US 2022/0361311 A1**(43) **Pub. Date: Nov. 10, 2022**(54) **SHOCK WAVE VISUALIZATION FOR  
EXTREME ULTRAVIOLET PLASMA  
OPTIMIZATION**(71) Applicant: **TAIWAN SEMICONDUCTOR  
MANUFACTURING COMPANY,  
LTD.**, Hsinchu (TW)(72) Inventors: **Yen-Shuo SU**, Hsinchu City (TW);  
**Jen-Hao YEH**, Hsinchu City (TW);  
**Jhan-Hong YEH**, Hsinchu (TW);  
**Ting-Ya CHENG**, Taipei (TW);  
**Yee-Shian Henry TONG**, Hsinchu  
(TW); **Chun-Lin CHANG**, Zhubei City  
(TW); **Han-Lung CHANG**, Kaohsiung  
City (TW); **Li-Jui CHEN**, Hsinchu  
City (TW); **Po-Chung CHENG**,  
Longxing Village (TW)(21) Appl. No.: **17/874,278**(22) Filed: **Jul. 26, 2022****Related U.S. Application Data**(63) Continuation of application No. 16/655,116, filed on  
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(2013.01)(57) **ABSTRACT**

A method for monitoring a shock wave in an extreme ultraviolet light source includes irradiating a target droplet in the extreme ultraviolet light source apparatus of an extreme ultraviolet lithography tool with ionizing radiation to generate a plasma and to detect a shock wave generated by the plasma. One or more operating parameters of the extreme ultraviolet light source is adjusted based on the detected shock wave.

